

Applicant: Lih-Ping Li
Serial No.: 10/810,912
Attorney Docket No.: 67,200-1256

IN THE SPECIFICATION

Please amend the abstract of the disclosure as follows.

Abstract of the Disclosure

A ~~newel~~ method for seasoning a process chamber to substantially ~~reduce the quantity of particulate residues remaining in the chamber after semiconductor fabrication or other processes are carried out in the chamber,~~ is disclosed. The seasoning method includes providing a seasoning film on the interior surfaces of a process chamber, typically after cleaning of the chamber. Accordingly, ~~the quantity of particulate by-product residues which remain in the chamber after processing is substantially reduced.~~